

AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1-19 (withdrawn)

20 (original). A process for fabricating an electrically modulated programmable mask operable at lithographic wavelengths comprising:

providing a substrate having electrical control circuitry thereon; and

applying nano-particles to at least a portion of said substrate.

21-26 (withdrawn)

27. (original) The process of claim 20 wherein said substrate comprises silicon-on-sapphire.

28-39 (withdrawn)